

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	12	(("6784312") or ("4690993") or ("4633003") or ("20030194650") or ("6852467") or ("5716756")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/02/20 15:27
L2	3	("3179640").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/02/20 15:31
L3	451	(\$hydroxy near2 hexafluoroisopropyl near2 styrene) or hfs! or (hydroxyfluoroalkylstyrene) or (hydroxyfluoroalkyl near2 substituted near2 styrene)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:42
L4	10603052	copper or cu! or iron or fe! or cobalt or co! or nickel or ni! or rhodium or rh! or palladium or pd! or ruthenium or ru! or platinum or pt!	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:37
L5	380	I3 and I4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:37
L6	56070	phosphine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:37
L7	856273	hydroxide or carbonate or bicarbonate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:39
L8	572696	amine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:39
L9	4478696	base	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:39

L10	131	I5 and (I7 or I9)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:40
L11	4	I10 and (I6 or I8)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 15:41
L12	14	(\$5hydroxy near2 hexafluoroisopropyl near2 styrene) or (hydroxyfluoroalkylstyrene) or (hydroxyfluoroalkyl near2 substituted near2 styrene)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/20 16:50
L13	2	("20030232940").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/02/20 16:50

10/600,510

alerts (SDIs) affected
NEWS 10 DEC 17 COMPUAB reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 11 DEC 17 SOLIDSTATE reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 12 DEC 17 CERAB reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 13 DEC 17 THREE NEW FIELDS ADDED TO IFIPAT/IFIUDB/IFICDB
NEWS 14 DEC 30 EPFULL: New patent full text database to be available on STN
NEWS 15 DEC 30 CAPLUS - PATENT COVERAGE EXPANDED
NEWS 16 JAN 03 No connect-hour charges in EPFULL during January and
February 2005
NEWS 17 JAN 26 CA/CAPLUS - Expanded patent coverage to include the Russian
Agency for Patents and Trademarks (ROSPATENT)
NEWS 18 FEB 10 STN Patent Forums to be held in March 2005
NEWS 19 FEB 16 STN User Update to be held in conjunction with the 229th ACS
National Meeting on March 13, 2005

NEWS EXPRESS JANUARY 10 CURRENT WINDOWS VERSION IS V7.01a, CURRENT
MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
AND CURRENT DISCOVER FILE IS DATED 10 JANUARY 2005

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 14:33:47 ON 20 FEB 2005

=> FIL STNGUIDE

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'STNGUIDE' ENTERED AT 14:33:51 ON 20 FEB 2005

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FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Feb 18, 2005 (20050218/UP).

=> file caplus

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.06	0.27

FILE 'CAPLUS' ENTERED AT 14:34:03 ON 20 FEB 2005

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FILE COVERS 1907 - 20 Feb 2005 VOL 142 ISS 9
FILE LAST UPDATED: 18 Feb 2005 (20050218/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> activate save

'SAVE' MUST END IN '/Q', '/A', '/L', '/S', OR '/B'

The name of a saved query (or structure or screen set) ends in '/Q'. The name of a saved answer set ends in '/A'. The name of a saved L# list ends in '/L'. The name of an SDI request ends in '/S'. The name of a BATCH search request ends in '/B'. You must enter the /Q, /A, /L, /S, or /B at the end of the name.

ENTER NAME OF SAVED ITEM TO ACTIVATE OR (END):save/a

'SAVE/A' IS NOT A VALID SAVED NAME

Enter "HELP SAVED NAMES" at an arrow prompt (=>) to see a list of rules for saved names. Enter "DISPLAY SAVED" at an arrow prompt (=>) to see a list of all saved queries and answer sets for this loginid. To see a list of all SDI profiles, enter "DISPLAY SAVED/S". To see a list of BATCH search requests, enter "DISPLAY SAVED/B".

ENTER NAME OF SAVED ITEM TO ACTIVATE OR (END):end

=> activate save/a

'SAVE/A' IS NOT A VALID SAVED NAME

Enter "HELP SAVED NAMES" at an arrow prompt (=>) to see a list of rules for saved names. Enter "DISPLAY SAVED" at an arrow prompt (=>) to see a list of all saved queries and answer sets for this loginid. To see a list of all SDI profiles, enter "DISPLAY SAVED/S". To see a list of BATCH search requests, enter "DISPLAY SAVED/B".

ENTER NAME OF SAVED ITEM TO ACTIVATE OR (END):display saved

'DISPLAY SAVED' IS NOT A VALID SAVED NAME

Enter "HELP SAVED NAMES" at an arrow prompt (=>) to see a list of rules for saved names. Enter "DISPLAY SAVED" at an arrow prompt (=>) to see a list of all saved queries and answer sets for this loginid. To see a list of all SDI profiles, enter "DISPLAY SAVED/S". To see a list of BATCH search requests, enter "DISPLAY SAVED/B".

ENTER NAME OF SAVED ITEM TO ACTIVATE OR (END):activate styrene/a

'ACTIVATE STYRENE/A' IS NOT A VALID SAVED NAME

Enter "HELP SAVED NAMES" at an arrow prompt (=>) to see a list of rules for saved names. Enter "DISPLAY SAVED" at an arrow prompt (=>) to see a list of all saved queries and answer sets for this loginid. To see a list of all SDI profiles, enter "DISPLAY SAVED/S". To see a list of BATCH search requests, enter "DISPLAY SAVED/B".

ENTER NAME OF SAVED ITEM TO ACTIVATE OR (END):end

=> activate styrene/a

L1 STR

L2 (669)SEA FILE=REGISTRY SSS FUL L1

10/600,510

L3 131 SEA FILE=CAPLUS L2/PREP

=> d his

(FILE 'HOME' ENTERED AT 14:33:47 ON 20 FEB 2005)

FILE 'STNGUIDE' ENTERED AT 14:33:51 ON 20 FEB 2005

FILE 'CAPLUS' ENTERED AT 14:34:03 ON 20 FEB 2005
ACTIVATE STYRENE/A

L1 STR
L2 (669)SEA FILE=REGISTRY SSS FUL L1
L3 131 SEA FILE=CAPLUS L2/PREP

=> s l3 and (copper or iron or cobalt or nickel or rhodium or palladium or ruthenium or platinum)

833345 COPPER
911886 IRON
346425 COBALT
569450 NICKEL
64200 RHODIUM
146250 PALLADIUM
82540 RUTHENIUM
187463 PLATINUM

L4 3 L3 AND (COPPER OR IRON OR COBALT OR NICKEL OR RHODIUM OR PALLADIUM OR RUTHENIUM OR PLATINUM)

=> d 1-3 ti

L4 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2005 ACS on STN

TI Process for producing fluorine-containing, polymerizable styrene monomer and intermediates used in same

L4 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2005 ACS on STN

TI Polymeric materials absorbing organophosphorus compounds, their synthesis, and chemical sensors containing these materials

L4 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2005 ACS on STN

TI The synthesis and attempted polymerization of an α,β,β -trifluorostyrene disubstituted by hexafluoro-2-propyl groups

=> d l3 1-131 ti

L3 ANSWER 1 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working photoresist composition containing alkali-soluble fluorine-containing polymer

L3 ANSWER 2 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

TI Cyclic fluorine compounds, polymerizable fluoromonomers, fluoropolymers, and resist materials containing the fluoropolymers and method for pattern formation

L3 ANSWER 3 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

TI Novel polymerizable acrylate compound containing hexafluorocarbinol group and polymer made therefrom

L3 ANSWER 4 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive resist compositions for patterning using vacuum-ultraviolet ray

- L3 ANSWER 5 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition containing specific resin and method for pattern formation using the same
- L3 ANSWER 6 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition containing specific resin
- L3 ANSWER 7 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified positive photoresist compositions with good alkali developability, line edge roughness, and transparency to F2 excimer laser beams
- L3 ANSWER 8 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive resist composition
- L3 ANSWER 9 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Photosensitive resin composition
- L3 ANSWER 10 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluorinated cyclic compound, polymerizable fluoromonomer, fluoropolymer, resist material comprising the same, and method of forming pattern with the same
- L3 ANSWER 11 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working vacuum-UV photoresist composition and patterning method using the same
- L3 ANSWER 12 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working resist composition containing alkali-soluble resins and photoacids
- L3 ANSWER 13 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working resist composition containing alkali soluble resins and photoacids
- L3 ANSWER 14 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified photoresist composition
- L3 ANSWER 15 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified photoresist composition containing specific photoacid generator and specific fluoro polymers
- L3 ANSWER 16 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition for 157 nm photolithography
- L3 ANSWER 17 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive resist composition
- L3 ANSWER 18 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluorine compounds bearing acid-labile groups, their manufacture, and photoresists, and pattern forming method using the photoresists
- L3 ANSWER 19 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive resist composition and method of forming a resist pattern using the same
- L3 ANSWER 20 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working resist composition containing cyclic ether compound
- L3 ANSWER 21 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive resist composition with wide exposure latitude

- L3 ANSWER 22 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Cyclic ethers and positive resist compositions
- L3 ANSWER 23 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Sulfonates, polymers, resist compositions and patterning process
- L3 ANSWER 24 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Photosensitive polymer including fluorine, resist composition containing the same and patterning method using the resist composition
- L3 ANSWER 25 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition
- L3 ANSWER 26 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified resist composition, its manufacture, and patterning method
- L3 ANSWER 27 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition containing specific fluoro resin
- L3 ANSWER 28 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified positive resist compositions with improved line edge roughness and suppressed scum generation
- L3 ANSWER 29 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluorine-containing compounds as dissolution inhibitors and intermediates for monomers, and their polymers for resists
- L3 ANSWER 30 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working resist composition containing base compound having one or more cyclic ether group for improved line edge roughness
- L3 ANSWER 31 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluorocarbon polymer-based photoresists for 157-nm lithography
- L3 ANSWER 32 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI The influence of hydrogen bonding on the preparation and mechanical properties of PS-diblock copolymer blends
- L3 ANSWER 33 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Novel organosilicon copolymer and photoresist compositions for deep UV bilayer system
- L3 ANSWER 34 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Photosensitive composition and acid generator
- L3 ANSWER 35 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working resist composition with improved precision in response to light
- L3 ANSWER 36 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemical amplification type photoresist composition
- L3 ANSWER 37 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-type resist compositions with reduced out-gas emission for vacuum UV microlithography
- L3 ANSWER 38 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluoro compounds, their polymers, and their use for antireflective films and resist materials
- L3 ANSWER 39 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

- TI Radical copolymerization of 2-trifluoromethylacrylic monomers. III. Kinetics and monomer reactivities in the copolymerization of t-butyl 2-trifluoromethylacrylate and methacrylate with styrene bearing hexafluoroisopropanol

- L3 ANSWER 40 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Chemically amplified photoresists and method for pattern formation

- L3 ANSWER 41 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Hydrophilic vinylsulfonate derivative polymers, resist compositions and patterning process

- L3 ANSWER 42 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorinated polymer

- L3 ANSWER 43 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition containing specific resin

- L3 ANSWER 44 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photosensitive resin composition

- L3 ANSWER 45 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Process for producing fluorine-containing, polymerizable styrene monomer and intermediates used in same

- L3 ANSWER 46 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive photoresist composition

- L3 ANSWER 47 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photosensitive polymer including fluorine and resist composition containing the same

- L3 ANSWER 48 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Acetal protected polymers for photoresists compositions

- L3 ANSWER 49 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition

- L3 ANSWER 50 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition containing specific resin

- L3 ANSWER 51 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photosensitive resin composition for photolithography

- L3 ANSWER 52 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition

- L3 ANSWER 53 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Novel esters, polymers, resist compositions and patterning process

- L3 ANSWER 54 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Polymers, resist compositions and patterning process

- L3 ANSWER 55 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Chemically amplified positive photoresists for ≤ 160 nm vacuum UV lithography

- L3 ANSWER 56 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Sulfonium compounds as radiation-sensitive acid generators and resist compositions containing them

- L3 ANSWER 57 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

- TI Chemically amplified photoresist compositions with high sensitivity and resolution
- L3 ANSWER 58 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Radiation sensitive composition and compound
- L3 ANSWER 59 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working chemically amplified photoresist composition containing specific polymer
- L3 ANSWER 60 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Photoresist composition containing specific resin
- L3 ANSWER 61 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working chemically amplified photoresists containing specific resin
- L3 ANSWER 62 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working chemically amplified photoresists containing specific resin
- L3 ANSWER 63 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working chemically amplified photoresists containing specific resin
- L3 ANSWER 64 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive resist composition
- L3 ANSWER 65 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition
- L3 ANSWER 66 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive-working photoresist composition containing polymer with fluoro-aliphatic group
- L3 ANSWER 67 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Protecting groups for lithographic resist compositions
- L3 ANSWER 68 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Polymer blend and associated methods of preparation and use
- L3 ANSWER 69 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Chemically amplified photoresists for ≤ 180 -nm photolithography, polymers therefor, and fluorine-containing acetals or ketals as monomers thereof
- L3 ANSWER 70 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Positive photoresists having high transparency to 157-nm light, minimum edge roughness, and wide development latitude
- L3 ANSWER 71 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Photosensitive resin composition
- L3 ANSWER 72 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Fluorine-containing styrene derivatives and their preparation, macromolecular compounds, antireflection coating materials and chemically amplified resist materials
- L3 ANSWER 73 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI A new photoresist materials for 157 nm lithography-3: Poly[2-hydroxy-3-pinanyl vinyl sulfonate-co-4-(1,1,1,3,3,3-hexafluoro-2-hydroxypropyl)styrene]

- L3 ANSWER 74 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive resist compositions using fluorine-containing copolymers

- L3 ANSWER 75 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Evaluation of fluorinated dissolution inhibitors for 157-nm lithography

- L3 ANSWER 76 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photosensitive fluoropolymer having hydrate structure and resist composition thereof

- L3 ANSWER 77 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photosensitive polymers having high transmittance and improved dry etching resistance and chemically amplified resist compositions containing the same

- L3 ANSWER 78 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working resist composition containing specific fluorine group-containing resin

- L3 ANSWER 79 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Chemically amplified positive resists forming defect-free patterns by deep-UV lithography using F2 excimer lasers

- L3 ANSWER 80 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition containing fluoro-substituted nitrogen compound

- L3 ANSWER 81 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive photoresist composition

- L3 ANSWER 82 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Polymers for resists used in pattern formation with high energy beams

- L3 ANSWER 83 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI New Photoresist Materials for 157-nm Lithography. Poly[vinylsulfonyl fluoride-co-4-(1,1,1,3,3,3-hexafluoro-2-hydroxypropyl)-styrene] Partially Protected with tert-Butoxycarbonyl

- L3 ANSWER 84 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Vacuum UV-sensitive resin composition containing ionic compound reactive towards acid

- L3 ANSWER 85 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Polymers, resist compositions and patterning process

- L3 ANSWER 86 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorine-containing bicycloheptyl acrylates, their manufacture, their transparent polymers, and photoresists and antireflective materials using them

- L3 ANSWER 87 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorine-containing monomers and polymers for making reflective, optical, and resist materials

- L3 ANSWER 88 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Chemically amplified positive photoresist fluoropolymer compositions with high resolution and transparency to F2 excimer laser beams, and their deposition method

- L3 ANSWER 89 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working vacuum UV-sensitive photoresist material composition

containing specific resin

- L3 ANSWER 90 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive resist composition

- L3 ANSWER 91 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorine-containing polymers, resist materials containing the polymers, and pattern formation using the materials

- L3 ANSWER 92 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Chemically amplified positive resists, their acid-labile polymers, and deep-UV or soft x-ray lithography thereon

- L3 ANSWER 93 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorine-containing styrene acrylate copolymers and use thereof in lithographic photoresist compositions

- L3 ANSWER 94 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Polymers with fluorinated styrene-based mer units, their positive resist materials, and their patterning

- L3 ANSWER 95 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Investigation of a fluorinated ESCAP-based resist for 157-nm lithography

- L3 ANSWER 96 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Highly transparent resist platforms for 157-nm microlithography: an update

- L3 ANSWER 97 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Photoresist compositions for excimer laser lithography

- L3 ANSWER 98 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive resist composition containing resin and photoacid generator

- L3 ANSWER 99 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Low absorbing resists for 157 nm photolithography

- L3 ANSWER 100 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI A new photoresist material for 157 nm lithography-2

- L3 ANSWER 101 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI New strategies for high resolution photoresists

- L3 ANSWER 102 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive-working photoresist composition containing specific binder resin

- L3 ANSWER 103 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Design and syntheses of mass persistent photoresists

- L3 ANSWER 104 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Fluorocarbon polymer-based photoresists for 157-nm lithography

- L3 ANSWER 105 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Transparent fluorine-containing copolymers for materials for plastic optical fibers and optical waveguides

- L3 ANSWER 106 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Block-Copolymer-Free Strategy for Preparing Micelles and Hollow Spheres: Self-Assembly of Poly(4-vinylpyridine) and Modified Polystyrene

- L3 ANSWER 107 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
- TI Positive resist composition

- L3 ANSWER 108 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Lithographic production of stamper for optical disk by using x ray-sensitive positive-working resist as mask
- L3 ANSWER 109 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Tailoring transparency of imageable fluoropolymers at 157 nm by incorporation of hexafluoroisopropyl alcohol to photoresist backbones
- L3 ANSWER 110 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Development of 157 nm positive resists
- L3 ANSWER 111 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Dissolution behavior of fluoroalcohol-substituted polystyrenes
- L3 ANSWER 112 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Characterization of new aromatic polymers for 157-nm photoresist applications
- L3 ANSWER 113 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Polymer design for 157-nm chemically amplified resists
- L3 ANSWER 114 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI 157 nm single-layer and bilayer resists based on α -methylstyrene polymers
- L3 ANSWER 115 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Rejuvenation of 248 nm resist backbones for 157 nm lithography
- L3 ANSWER 116 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Novel fluoropolymers for use in 157 nm lithography
- L3 ANSWER 117 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Studies on complexation-induced micellization of block-graft copolymer SEPG and PS(OH)
- L3 ANSWER 118 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Polymeric materials absorbing organophosphorus compounds, their synthesis, and chemical sensors containing these materials
- L3 ANSWER 119 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Preparation of phenylalanine derivatives as antiinflammatory agents
- L3 ANSWER 120 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI The effects of hydrogen bonding on the miscibility, complexation, and crystallization in blends of crystalline and amorphous components
- L3 ANSWER 121 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Positive type photosensitive materials for microlenses
- L3 ANSWER 122 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Sulfonic acid esters, their production and photosensitive compositions containing them.
- L3 ANSWER 123 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Controllable specific interactions and miscibility in polymer blends: 4. Effect of hydrogen bonding density in interpenetrating polymer networks
- L3 ANSWER 124 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Negative-working photosensitive composition and its use
- L3 ANSWER 125 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 TI Styrene derivatives bearing substituted hexafluoroisopropyl groups

10/600,510

L3 ANSWER 126 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Synthesis and evaluation of hexafluorodimethylcarbinol functionalized polymers as microsensor coatings

L3 ANSWER 127 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI The synthesis and attempted polymerization of an α,β,β -trifluorostyrene disubstituted by hexafluoro-2-propyl groups

L3 ANSWER 128 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI 4-(2-hydroxyhexafluoroisopropyl)styrene monomer for ophthalmic applications

L3 ANSWER 129 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Polymer compatibilization through hydrogen bonding

L3 ANSWER 130 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Polymer blends containing hydrogen bonding

L3 ANSWER 131 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
TI Phenylpropionamide and phenylpropionate derivatives

=> file stnguide

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	60.70	60.97

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FILE CONTAINS CURRENT INFORMATION.
LAST RELOADED: Feb 18, 2005 (20050218/UP).

=> file caplus

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.66	61.63

FILE 'CAPLUS' ENTERED AT 14:44:03 ON 20 FEB 2005
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FILE COVERS 1907 - 20 Feb 2005 VOL 142 ISS 9
FILE LAST UPDATED: 18 Feb 2005 (20050218/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

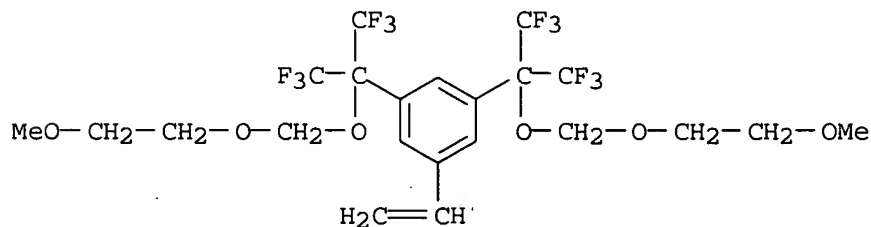
10/600,510

=> d 13 1,29,38,72,87,125,127,128 bib fhitr

L3 ANSWER 1 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:57546 CAPLUS
DN 142:144071
TI Positive-working photoresist composition containing alkali-soluble
fluorine-containing polymer
IN Kanda, Hiromi; Mizutani, Kazuyoshi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 41 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2005017729	A2	20050120	JP 2003-182848	20030626
PRAI	JP 2003-182848		20030626		
IT	756532-35-1P				

RL: RCT (Reactant); SPN (Synthetic preparation); **PREP**
(**Preparation**); RACT (Reactant or reagent)
(preparation of alkali-soluble fluorine-containing polymer for photoresist
composition)
RN 756532-35-1 CAPLUS
CN Benzene, 1-ethenyl-3,5-bis[2,2,2-trifluoro-1-[(2-methoxyethoxy)methoxy]-1-
(trifluoromethyl)ethyl]- (9CI) (CA INDEX NAME)



L3 ANSWER 29 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:631706 CAPLUS
DN 141:181965
TI Fluorine-containing compounds as dissolution inhibitors and intermediates
for monomers, and their polymers for resists
IN Narita, Tadashi; Maeda, Kazuhiko
PA Central Glass Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 22 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004217533	A2	20040805	JP 2003-4262	20030110
	US 2004192867	A1	20040930	US 2004-753071	20040108
PRAI	JP 2003-4262	A	20030110		
OS	MARPAT 141:181965				
IT	733049-95-1P				

RL: IMF (Industrial manufacture); TEM (Technical or engineered material
use); **PREP** (**Preparation**); USES (Uses)

10/600,510

(F-containing compds. as monomers and dissoln. inhibitors, and polymers for resists showing good vacuum-UV transparency, etching resistance, and adhesion to substrates)

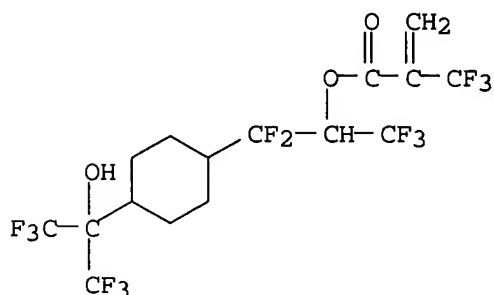
RN 733049-95-1 CAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1-[difluoro[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]methyl]-2,2,2-trifluoroethyl ester, polymer with 1-ethenyl-3,5-bis[2,2,2-trifluoro-1-(methoxymethoxy)-1-(trifluoromethyl)ethyl]benzene (9CI) (CA INDEX NAME)

CM 1

CRN 733049-94-0

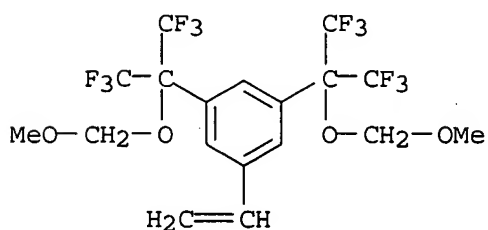
CMF C16 H14 F14 O3



CM 2

CRN 585573-59-7

CMF C18 H16 F12 O4



L3 ANSWER 38 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:217351 CAPLUS

DN 140:254360

TI Fluoro compounds, their polymers, and their use for antireflective films and resist materials

IN Kadota, Shinichi; Komoritani, Haruhiko; Maeda, Kazuhiko

PA Central Glass Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 30 pp.

CODEN: JKXXAF

DT Patent

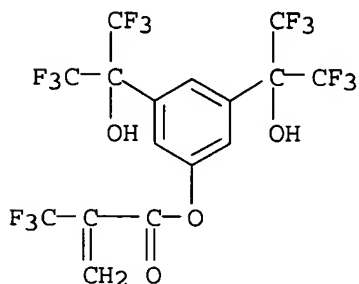
LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004083900	A2	20040318	JP 2003-279778	20030725
	US 2004106755	A1	20040603	US 2003-634997	20030806
PRAI	JP 2002-229552	A	20020807		

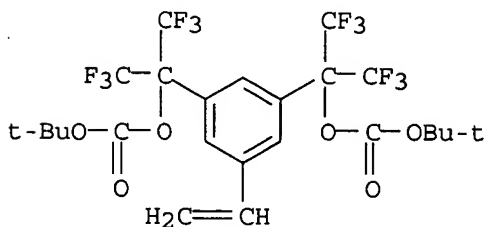
10/600,510

OS MARPAT 140:254360
IT 669768-46-1P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); **PREP (Preparation)**; USES (Uses)
(fluoro compds., their polymers, and their use for antireflective films and resist materials)
RN 669768-46-1 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 3,5-bis[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]phenyl ester, polymer with (5-ethenyl-1,3-phenylene)bis[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene] bis(1,1-dimethylethyl carbonate) (9CI) (CA INDEX NAME)
CM 1
CRN 669768-32-5
CMF C16 H7 F15 O4



CM 2

CRN 585573-38-2
CMF C24 H24 F12 O6



L3 ANSWER 72 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:671118 CAPLUS
DN 139:205035
TI Fluorine-containing styrene derivatives and their preparation,
macromolecular compounds, antireflection coating materials and chemically
amplified resist materials
IN Komoritani, Haruhiko; Tsunoda, Shinichi; Otani, Mitsutaka; Maeda, Kazuhiko
PA Central Glass Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 19 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.

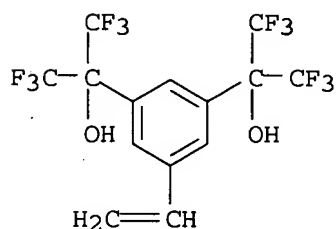
KIND

DATE

APPLICATION NO.

DATE

PI JP 2003238620 A2 20030827 JP 2002-125505 20020426
 US 2003232940 A1 20031218 US 2002-316183 20021211
 PRAI JP 2001-380776 A 20011213
 JP 2002-125505 A 20020426
 OS MARPAT 139:205035
 IT **568587-26-8P**
 RL: IMF (Industrial manufacture); RCT (Reactant); **PREP**
 (**Preparation**); RACT (Reactant or reagent)
 (preparation of CF₃- and HO-substituted styrene derivs. and their macromol.
 compds., antireflection coatings and chemical amplified resists)
 RN 568587-26-8 CAPLUS
 CN 1,3-Benzenedimethanol, 5-ethenyl- $\alpha,\alpha,\alpha',\alpha'$ -
 tetrakis(trifluoromethyl)- (9CI) (CA INDEX NAME)



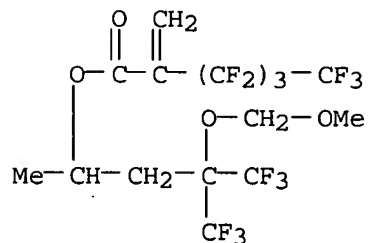
L3 ANSWER 87 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2003:110864 CAPLUS
 DN 138:154324
 TI Fluorine-containing monomers and polymers for making reflective, optical,
 and resist materials
 IN Miyazawa, Satoru; Maeda, Kazuhiko; Tokuhisa, Kenji; Arai, Shoji
 PA Central Glass Co., Ltd., Japan; Tosoh F-Tech Inc.
 SO Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003040840	A2	20030213	JP 2001-222530	20010724
	US 2003078352	A1	20030424	US 2002-198044	20020719
	US 6784312	B2	20040831		
	TW 593274	B	20040621	TW 2002-91116170	20020719
	US 2004236046	A1	20041125	US 2004-880097	20040630
PRAI	JP 2001-222530	A	20010724		
	US 2002-198044	A3	20020719		

OS MARPAT 138:154324
 IT **496064-91-6P**
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or
 engineered material use); **PREP** (**Preparation**); USES (Uses)
 (fluorine-containing monomers and polymers for making reflective, optical,
 and resist materials)
 RN 496064-91-6 CAPLUS
 CN Hexanoic acid, 3,3,4,4,5,5,6,6,6-nonafluoro-2-methylene-,
 4,4,4-trifluoro-3-(methoxymethoxy)-1-methyl-3-(trifluoromethyl)butyl
 ester, polymer with 4-ethenyl- α,α -
 bis(trifluoromethyl)benzenemethanol and 4-ethenylphenol (9CI) (CA INDEX
 NAME)

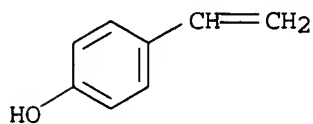
10/600,510

CRN 496064-75-6
CMF C15 H13 F15 O4



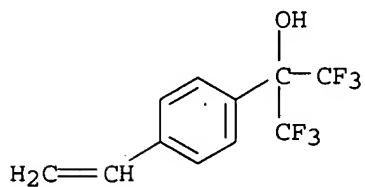
CM 2

CRN 2628-17-3
CMF C8 H8 O



CM 3

CRN 2386-82-5
CMF C11 H8 F6 O

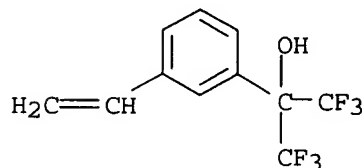


L3 ANSWER 125 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1994:165189 CAPLUS
DN 120:165189
TI Styrene derivatives bearing substituted hexafluoroisopropyl groups
IN Pawlowaski, Georg; Przybill, Klaus Juergen; Pawlowski, Georg
PA Hoechst A.-G., Germany
SO Ger. Offen., 8 pp.
CODEN: GWXXBX
DT Patent
LA German
FAN.CNT 1

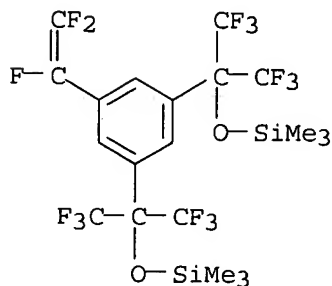
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4207261	A1	19930909	DE 1992-4207261	19920307
	DE 4207261	C2	20000316		
PRAI	DE 1992-4207261		19920307		

10/600,510

OS MARPAT 120:165189
IT 122056-08-0P
RL: PREP (Preparation)
(preparation of, for use in UV resists)
RN 122056-08-0 CAPLUS
CN Benzenemethanol, 3-ethenyl- α,α -bis(trifluoromethyl)- (9CI)
(CA INDEX NAME)



L3 ANSWER 127 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1991:558597 CAPLUS
DN 115:158597
TI The synthesis and attempted polymerization of an α,β,β -trifluorostyrene disubstituted by hexafluoro-2-propyl groups
AU Sprague, Lee G.; Snow, Arthur W.; Griffith, James R.
CS Chem. Div., Nav. Res. Lab., Washington, DC, 20375-5000, USA
SO Journal of Fluorine Chemistry (1991), 52(3), 301-6
CODEN: JFLCAR; ISSN: 0022-1139
DT Journal
LA English
OS CASREACT 115:158597
IT 136365-60-1P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and attempted polymerization of)
RN 136365-60-1 CAPLUS
CN Silane, [[5-(trifluoroethenyl)-1,3-phenylene]bis[[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]oxy]]bis[trimethyl- (9CI) (CA INDEX NAME)]



L3 ANSWER 128 OF 131 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1989:199252 CAPLUS
DN 110:199252
TI 4-(2-hydroxyhexafluoroisopropyl)styrene monomer for ophthalmic applications
IN Falcetta, Joseph J.; Park, Joonsup
PA Alcon Laboratories, Inc., USA
SO U.S., 10 pp. Cont.-in-part of U.S. Ser. No. 801,259.
CODEN: USXXAM
DT Patent
LA English

10/600,510

FAN.CNT 3

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4690993	A	19870901	US 1985-815439	19851231
	US 4633003	A	19861230	US 1985-801259	19851125
PRAI	US 1985-801259	A2	19851125		

IT 120245-51-4P

RL: PREP (Preparation)

(manufacture of, for oxygen-permeable hard contact lenses)

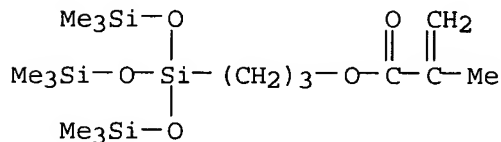
RN 120245-51-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol, methyl 2-methyl-2-propenoate and 3-[3,3,3-trimethyl-1,1-bis[(trimethylsilyl)oxy]disiloxanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 17096-07-0

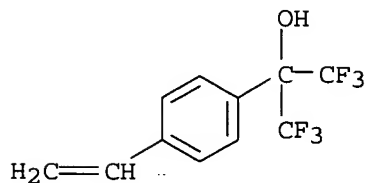
CMF C16 H38 O5 Si4



CM 2

CRN 2386-82-5

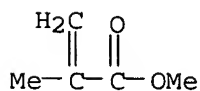
CMF C11 H8 F6 O



CM 3

CRN 80-62-6

CMF C5 H8 O2

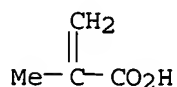


CM 4

CRN 79-41-4

CMF C4 H6 O2

10/600,510



=> file stnguide

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

27.57

89.20

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FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Feb 18, 2005 (20050218/UP).

=> log hold

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.30

89.50

SESSION WILL BE HELD FOR 60 MINUTES

STN INTERNATIONAL SESSION SUSPENDED AT 14:47:33 ON 20 FEB 2005

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:

* * * * * RECONNECTED TO STN INTERNATIONAL * * * * *

SESSION RESUMED IN FILE 'STNGUIDE' AT 14:58:02 ON 20 FEB 2005

FILE 'STNGUIDE' ENTERED AT 14:58:02 ON 20 FEB 2005

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AND TECHNOLOGY CORPORATION, AND FACHINFORMATIONSZENTRUM KARLSRUHE

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.30

89.50

=> file reg

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.30

89.50

FILE 'REGISTRY' ENTERED AT 14:58:15 ON 20 FEB 2005

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STRUCTURE FILE UPDATES: 18 FEB 2005 HIGHEST RN 834154-78-8
DICTIONARY FILE UPDATES: 18 FEB 2005 HIGHEST RN 834154-78-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

Please note that search-term pricing does apply when
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

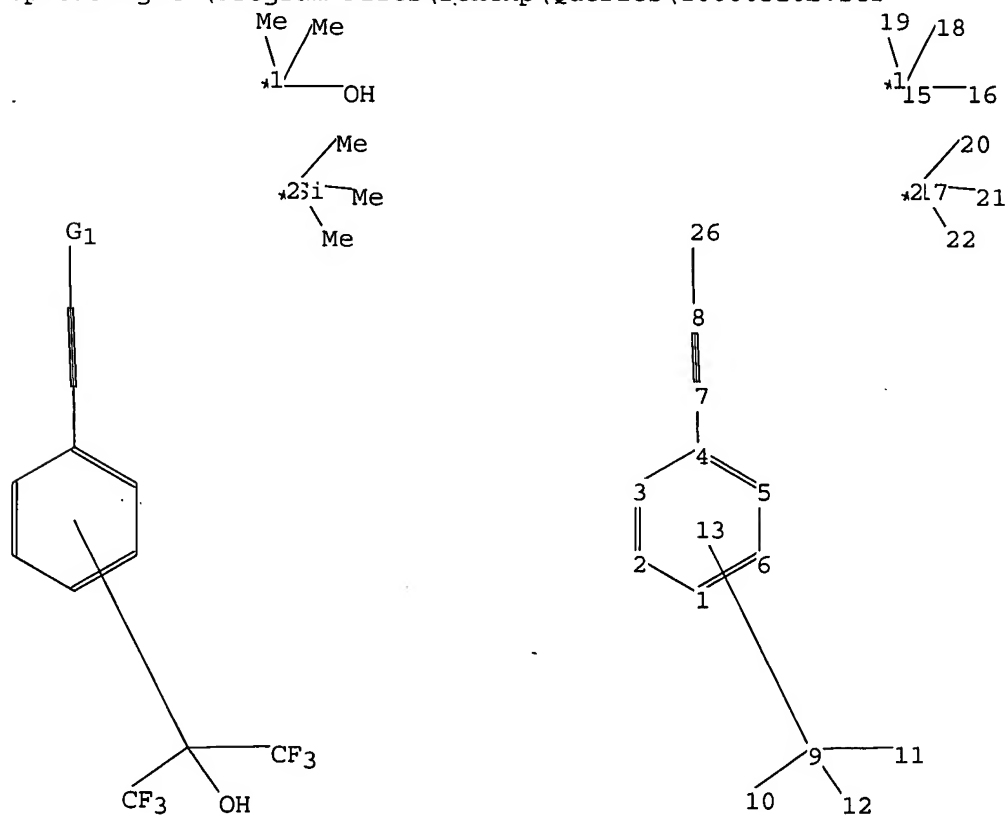
Experimental and calculated property data are now available. For more
information enter HELP PROP at an arrow prompt in the file or refer
to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10600510b.str



10/600,510

exact bonds :

4-7 7-8 9-10 9-11 15-18 15-19 17-20 17-21 17-22

normalized bonds :

1-2 1-6 2-3 3-4 4-5 5-6

isolated ring systems :

containing 1 :

G1:H, [*1], [*2]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 12:CLASS 13:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS
20:CLASS 21:CLASS 22:CLASS 26:CLASS

L5 STRUCTURE UPLOADED

=> que L5

L6 QUE L5

=> d

L6 HAS NO ANSWERS

L5 STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.

L6 QUE L5

=> s 16

SAMPLE SEARCH INITIATED 14:58:36 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED 0 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 0 TO 0

PROJECTED ANSWERS: 0 TO 0

L7 0 SEA SSS SAM L5

=> s 16 ful

FULL SEARCH INITIATED 14:58:45 FILE 'REGISTRY'

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100.0% PROCESSED 44 ITERATIONS

6 ANSWERS

SEARCH TIME: 00.00.01

L8 6 SEA SSS FUL L5

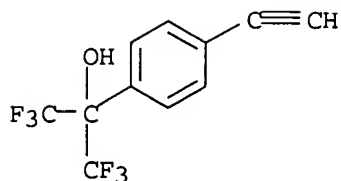
=> d scan

L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN

IN Benzenemethanol, 4-ethynyl- α,α -bis(trifluoromethyl)- (9CI)

MF C11 H6 F6 O

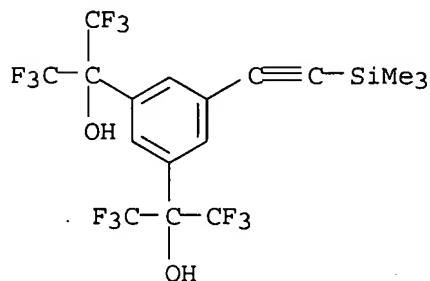
10/600,510



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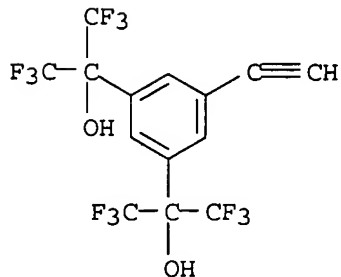
HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):5

L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN 1,3-Benzenedimethanol, α,α,α',α'-
tetrakis(trifluoromethyl)-5-[(trimethylsilyl)ethynyl]- (9CI)
MF C17 H14 F12 O2 Si



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

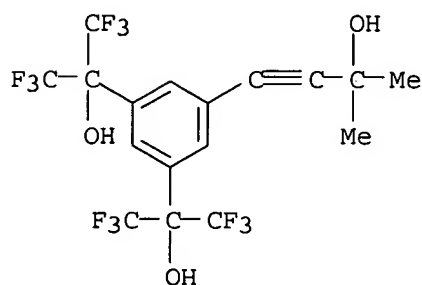
L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN 1,3-Benzenedimethanol, 5-ethynyl-α,α,α',α'-
tetrakis(trifluoromethyl)- (9CI)
MF C14 H6 F12 O2



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

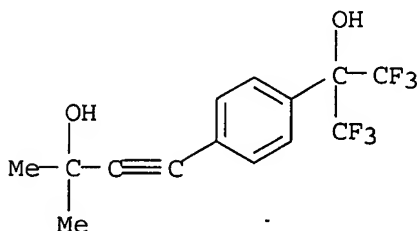
10/600,510

L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN 1,3-Benzenedimethanol, 5-(3-hydroxy-3-methyl-1-butynyl)-
 $\alpha,\alpha,\alpha',\alpha'$ -tetrakis(trifluoromethyl)- (9CI)
MF C17 H12 F12 O3



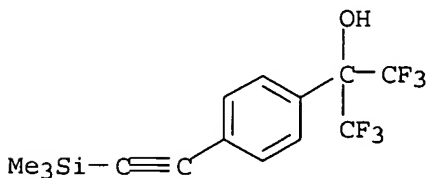
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN Benzenemethanol, 4-(3-hydroxy-3-methyl-1-butynyl)- α,α -
bis(trifluoromethyl)- (9CI)
MF C14 H12 F6 O2



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

L8 6 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN Benzenemethanol, α,α -bis(trifluoromethyl)-4-
[(trimethylsilyl)ethynyl]- (9CI)
MF C14 H14 F6 O Si



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

10/600,510

ALL ANSWERS HAVE BEEN SCANNED

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

161.76

251.26

FILE 'CAPLUS' ENTERED AT 14:59:38 ON 20 FEB 2005

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FILE COVERS 1907 - 20 Feb 2005 VOL 142 ISS 9

FILE LAST UPDATED: 18 Feb 2005 (20050218/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> s 18

L9 1 L8

=> d

L9 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:3703 CAPLUS

DN 140:60144

TI Process for producing fluorine-containing, polymerizable styrene monomer and intermediates used in same

IN Sumida, Shinichi; Kume, Takashi; Koga, Sunao; Komoriya, Haruhiko

PA Central Glass Company, Limited, Japan

SO U.S. Pat. Appl. Publ., 16 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	US 2004002612	A1	20040101	US 2003-600510	20030623
	JP 2004026691	A2	20040129	JP 2002-183138	20020624
PRAI	JP 2002-183138	A	20020624		
OS	MARPAT 140:60144				

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Connection closed by remote host

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